EAST Search History

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|----------|------|---|---|---------------------|---------|------------------|
| E | 1204 | (438/753):CCLS. | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/07/20 14:50 |
| L4 | 10 | semiconductor and substrate and ((dielectric or oxide or insulat\$4) adj (layer or film)) and ((tunable adj etch adj resistant adj (antireflective or anti-reflective)) or ("TERA")) and (via or hole or opening or open or trench or (dual damascene)) and (metal adj interconnect\$4) and @ad<="20031114" | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/07/20 15:17 |
| Si | 2469 | ((tunable adj etch adj resistant adj (antireflective or anti-reflective)) or ("TERA")) and (via or hole or opening or open or trench or (dual damascene)) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/07/20 11:01 |
| S2 | 222 | substrate and ((dielectric or oxide or insulat\$4) adj (layer or film)) and ((tunable adj etch adj resistant adj (antireflective or anti-reflective)) or ("TERA")) and (via or hole or opening or open or trench or (dual damascene)) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/07/19 14:22 |
| S3 | 112 | ((integrated adj circuit) or ("IC")) and substrate and ((dielectric or oxide or insulat\$4) adj (layer or film)) and ((tunable adj etch adj resistant adj (antireflective or anti-reflective)) or ("TERA")) and (via or hole or opening or open or trench or (dual damascene)) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/07/19 14:23 |
| S4 | 55 | ((integrated adj circuit) or ("IC")) and substrate and ((dielectric or oxide or insulat\$4) adj (layer or film)) and ((tunable adj etch adj resistant adj (antireflective or anti-reflective)) or ("TERA")) and (via or hole or opening or open or trench or (dual damascene)) and (interconnect\$4) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/07/19 14:26 |

EAST Search History

| | , | | T | · | , | |
|-----|------|--|---|----|-----|------------------|
| S5 | 12 | ((integrated adj circuit) or ("IC")) and substrate and ((dielectric or oxide or insulat\$4) adj (layer or film)) and ((tunable adj etch adj resistant adj (antireflective or anti-reflective)) or ("TERA")) and (via or hole or opening or open or trench or (dual damascene)) and (metal adj interconnect\$4) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/07/19 14:23 |
| \$6 | 8 | ((integrated adj circuit) or ("IC")) and substrate and ((dielectric or oxide or insulat\$4) adj (layer or film)) and ((tunable adj etch adj resistant adj (antireflective or anti-reflective)) or ("TERA")) and (via or hole or opening or open or trench or (dual damascene)) and (metal adj interconnect\$4) and @ad<="20031114" | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/07/20 15:17 |
| S7 | 8 | (("6,316,167") or ("6,573,030") or ("6,316,167") or ("6,309,955") or ("6,500,773") or ("6,117,619") or ("6,316,167") or ("6.620,727") or ("20030119307") or ("20040082173") or ("20050056940")).PN. | US-PGPUB; USPAT | OR | OFF | 2006/07/20 11:17 |
| S8 | 2679 | (438/637).CCLS. | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/07/20 11:15 |
| S9 | 984 | (438/638).CCLS. | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/07/20 11:15 |
| S10 | 418 | (438/695).CCLS: | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/07/20 11:16 |
| S11 | 791 | (438/785).CCLS. | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/07/20 11:16 |

EAST Search History

| S12 | 196 | (438/752).CCLS. | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/07/20 11:16 |
|-----|-----|---|---|----|-----|------------------|
| S14 | 2 | (("20050104150") or ("20050167839")) PN. | US-PGPUB; USPAT | UK | OFF | 2006/07/20 11:18 |